



[SC2] Plasma ALD / PECVD II	
Date / Time	July 28 (Sat.), 2018 / 10:50-12:30
Place	Room C (#114)
Session Chair(s)	Han-Bo-Ram Lee (Incheon Nat'l Univ., Korea)

SC2-1 [Invited] 10:50-11:15

Research in Thermal Area Selective Atomic Layer Deposition and Atomic Layer Etching for Advanced Device Patterning

Gregory Parsons

North Carolina State Univ., USA

SC2-2 [Invited] 11:15-11:40

ALD-Induced Blending of Polymers with Ceramics for Novel Functional Hybrids

Mato Knez

CIC nanoGUNE, Spain

SC2-3 [Invited] 11:40-12:05

Remote Plasma ALD for Low K Dielectric

Hyeongtag Jeon

Hanyang Univ., Korea

SC2-4 [Invited] 12:05-12:30

Plasma-Assisted Atomic Layer Deposition of SiN_x

Sumit Agarwal

Colorado School of Mines, USA